

## **Benchmark Technologies Announces PSFM Data!™: Focus Monitoring Data Analysis Software**

January 7, 2008, Benchmark Technologies (Lynnfield, MA) announced the availability of its PSFM Data!™ analysis software to support new and existing installations of its popular Phase Shift Focus Monitor (PSFM) reticle. The PSFM reticle is used by wafer fabrication facilities around the world to monitor focus conditions on wafer steppers and scanners. The reticle provides a speedy method of monitoring focus without disrupting production flows through the lithography cell by processing a single wafer lot and using offline overlay metrology common to most fabs. PSFM Data!™ augments the company's reticle offering and provides a complete turnkey solution for focus monitoring.

The software, which runs under Linux, Windows or Mac operating systems accepts input data streams for a variety of models of overlay metrology tools including KLA-Tencor, Nanometrics and others. The overlay data can be parsed and manipulated to output not only wafer focus plots, but also tilt, astigmatism and other lithography tool on-wafer performance data. Benchmark also provides a module to help users link the results of PSFM Data!™ analysis results to the user's statistical process control systems. Patrick Reynolds, Benchmark's President commented. "We are pleased to be able to offer our new and existing PSFM reticle customers another tool to help keep their fabs running at maximum efficiency."

### **About Benchmark Technologies:**

Benchmark Technologies, located in Lynnfield, MA provides lithographic test reticle design and fabrication services to the semiconductor, MEMS, disc drive, photonics and other industries. The company also provides consultative fabrication procurement services to companies that require precision complex pattern and relief structures by leveraging the semiconductor industry lithography infrastructure. More information can be found at the company website [www.benchmarktech.com](http://www.benchmarktech.com)